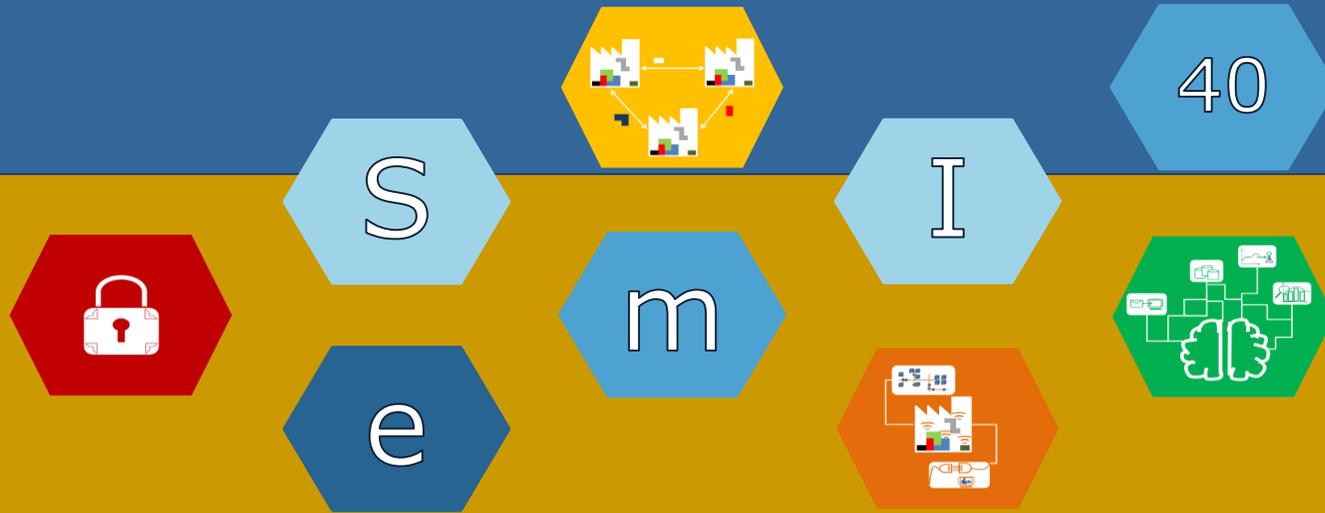


An Information-Theoretic Measure for Pattern Similarity in Analog Wafermaps

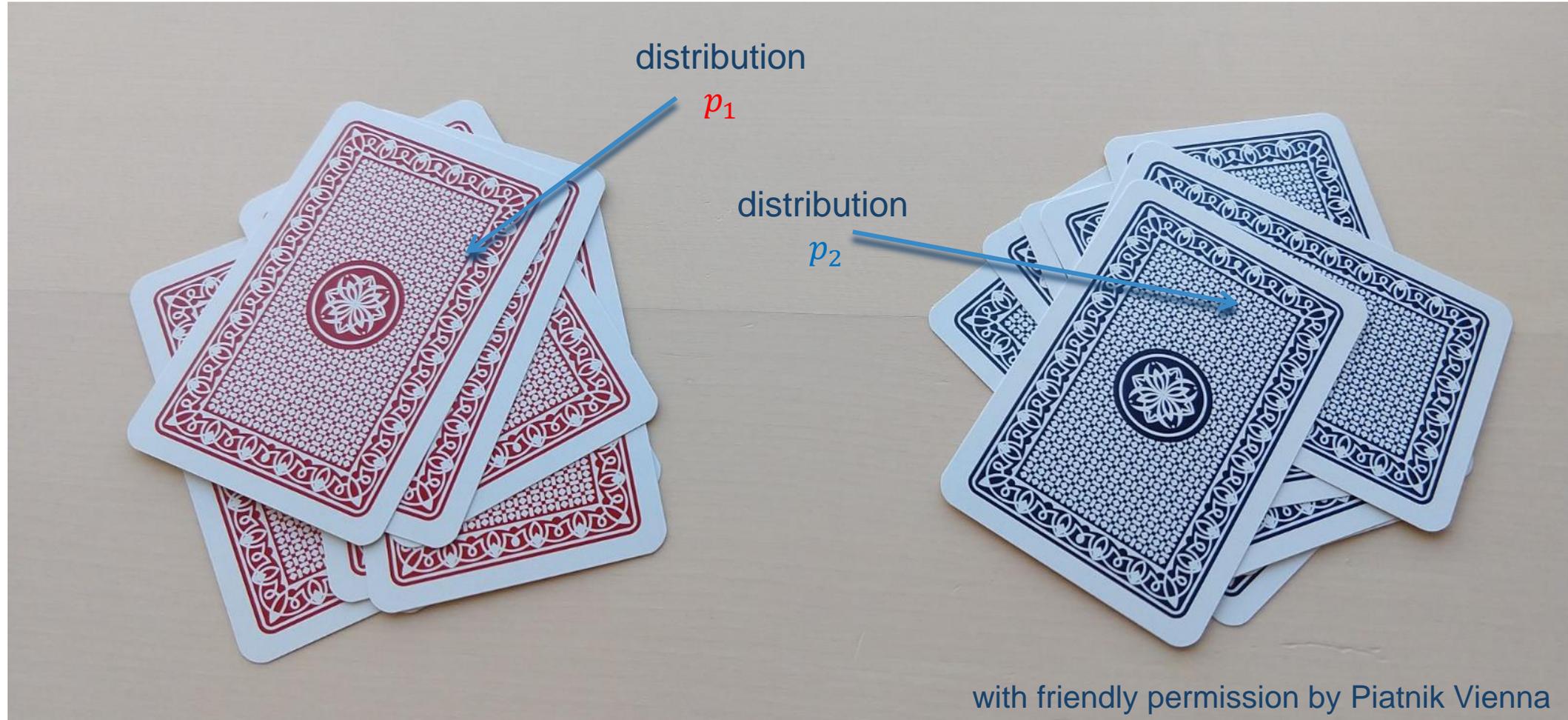
Bernhard C. Geiger,
Stefan Schrunner,
Roman Kern



Jensen-Shannon Divergence



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Jensen-Shannon Divergence



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$$JSD(W_1, W_2) := H\left(\frac{p_1 + p_2}{2}\right) - 0.5H(p_1) - 0.5H(p_2)$$

provides bounds on the Bayes error:

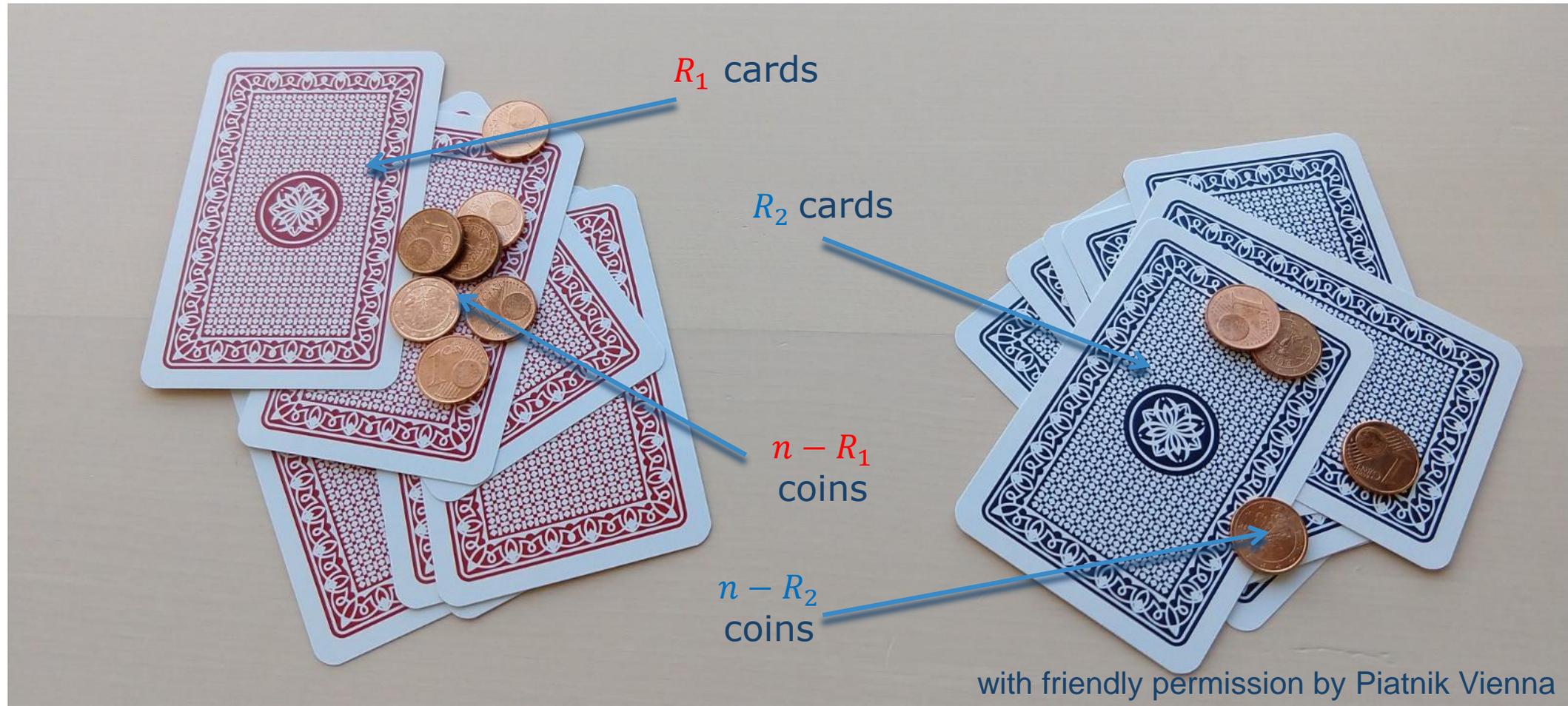
$$\frac{1}{4} (1 - JSD(W_1, W_2))^2 \leq P_{error} \leq \frac{1}{2} (1 - JSD(W_1, W_2))$$

J. Lin, "Divergence measures based on Shannon entropy," *IEEE Transactions on Information Theory*, vol. 37, no. 1, pp. 145-152, Jan 1991.

Jensen-Shannon Divergence



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Jensen-Shannon Divergence



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$$JSD(W_1, W_2) = \frac{R_1 + R_2}{2n} H\left(\frac{R_1 p_1 + R_2 p_2}{R_1 + R_2}\right) - \frac{R_1}{2n} H(p_1) - \frac{R_2}{2n} H(p_2) + JSD(r_1, r_2)$$

where r_i is Bernoulli- $\left(\frac{R_i}{n}, \frac{n-R_i}{n}\right)$.

B. C. Geiger, "A short note on the Jensen-Shannon divergence between simple mixture distributions," arXiv:1812.02059 [cs.IT], Dec 2018.

Jensen-Shannon Divergence



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$$JSD(W_1, W_2) = JSD(r_1, r_2)$$



Jensen-Shannon Divergence



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$$JSD(W_1, W_2) = \frac{R}{n} H\left(\frac{p_1 + p_2}{2}\right) - \frac{R}{2n} H(p_1) - \frac{R}{2n} H(p_2)$$



with friendly permission by Piatnik Vienna

Jensen-Shannon Divergence



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$$JSD(W_1, W_2) = 1$$



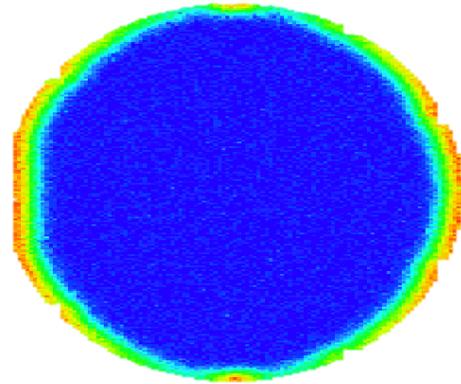
with friendly permission by Piatnik Vienna



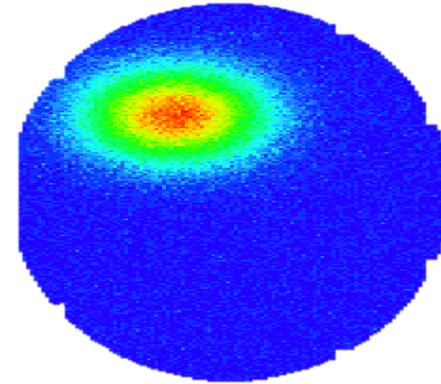
What's the point?

(What's the connection to semiconductor manufacturing?)

Are these two wafermaps similar?



W_1



W_2

→ Clustering, Classification, Novelty Detection



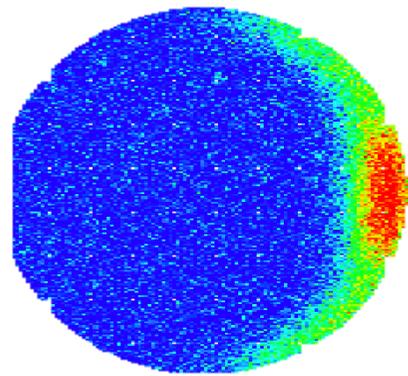
1. Denoising/Image Restoration
2. Determine „interesting“ regions on the wafer $\rightarrow R_1, R_2$
3. Represent each device in these regions by its relation to neighbors (“binary patterns”)
4. Compute distribution of binary patterns $\rightarrow p_1, p_2$
5. Compute similarity between wafermaps $\rightarrow JSD(W_1, W_2)$

T. Santos et al., “Feature Extraction from Analog Wafermaps: A Comparison of Classical Image Processing and a Deep Generative Model,” submitted to *IEEE Transactions on Semiconductor Manufacturing*.

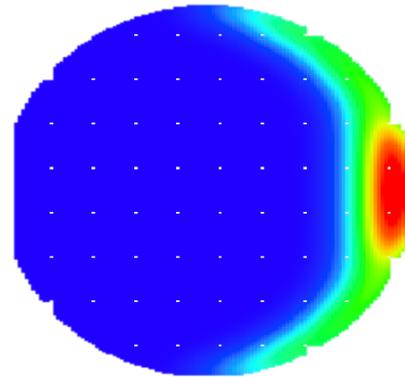
1. Denoising via Bayesian Inference



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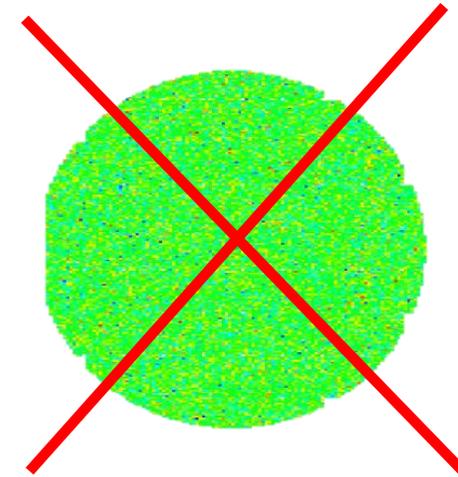


original wafermap



pattern

+



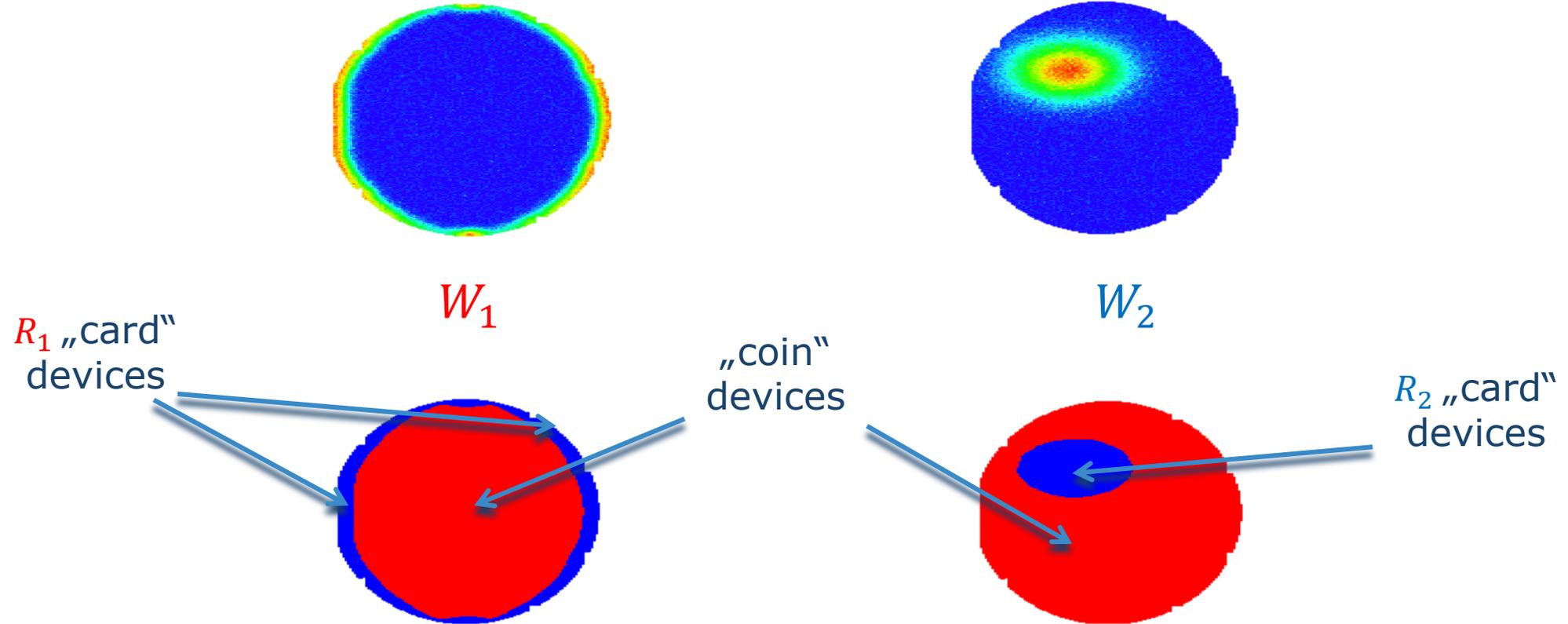
noise

S. Schrunner et al., "Markov Random Fields for Pattern Extraction in Analog Wafer Test Data," in *Proc. Int. Conf. on Image Processing Theory, Tools and Applications*, Montreal, pp. 1-6, Nov. 2017.

2. Determine Interesting Regions



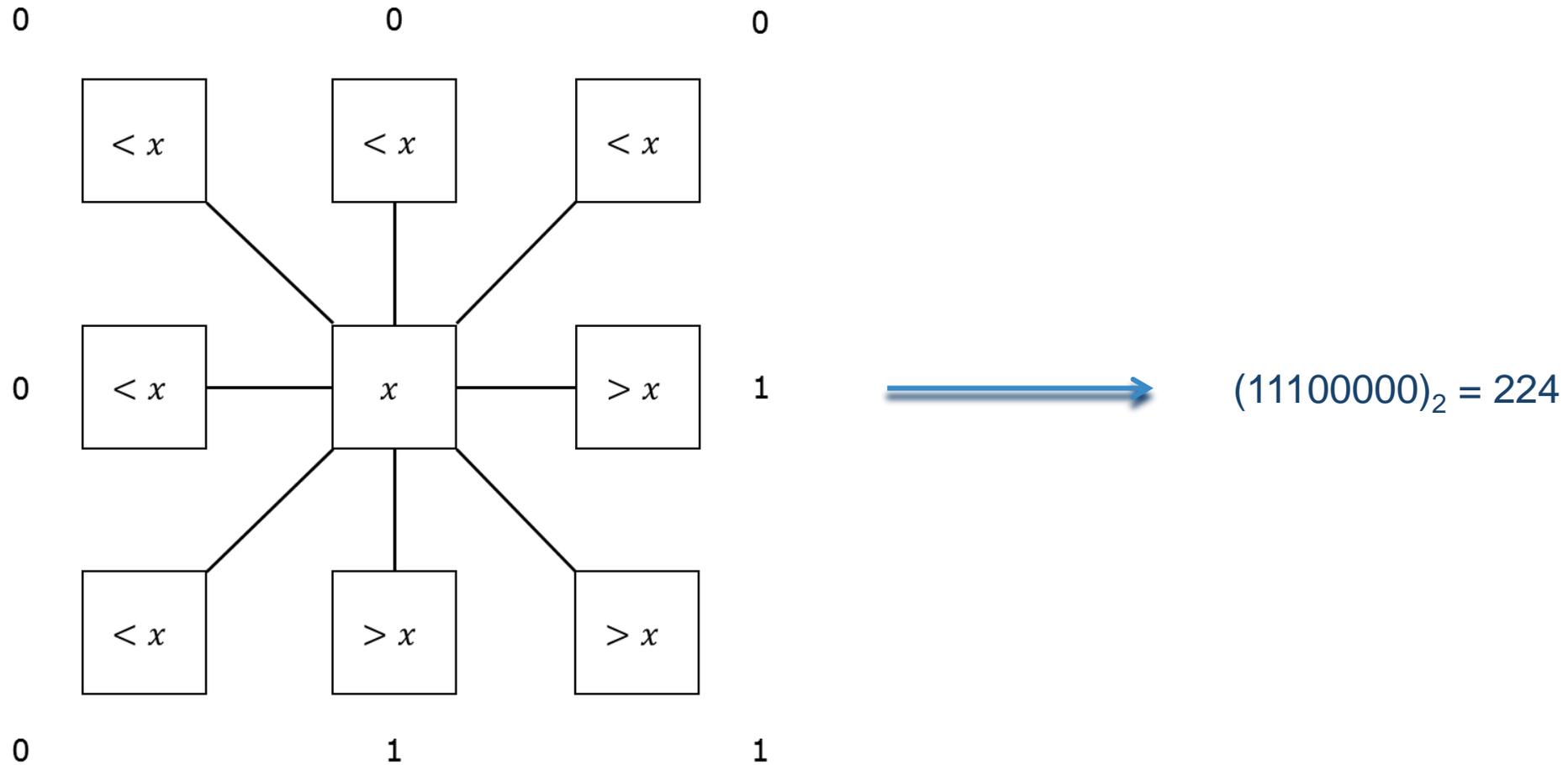
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3. Local Binary Patterns



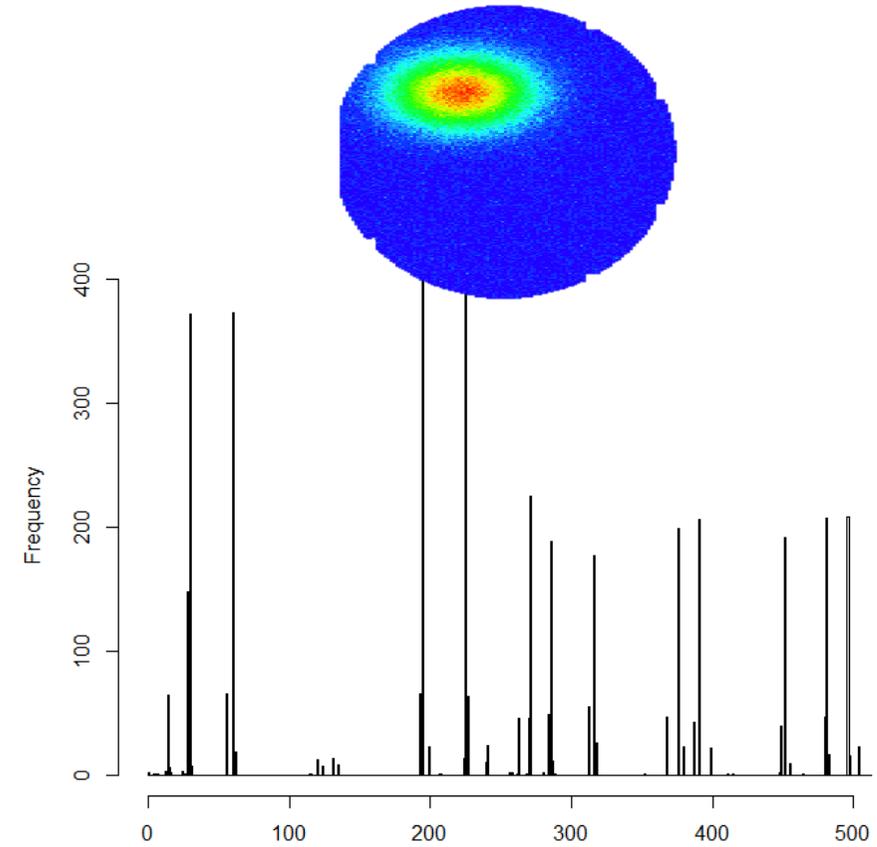
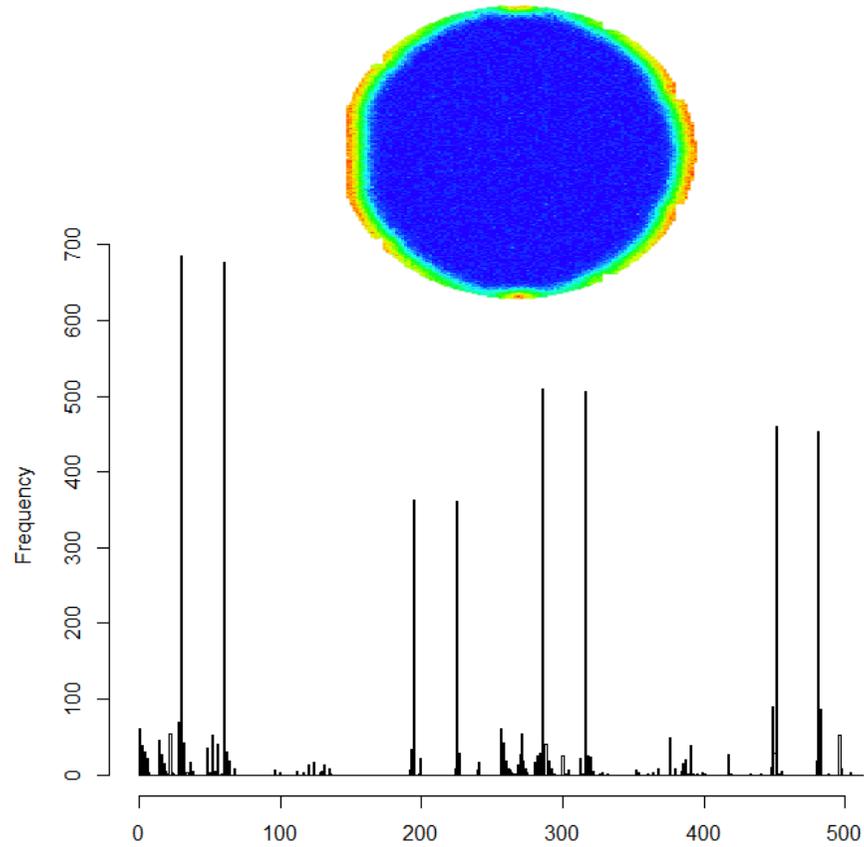
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4. Empirical Distributions



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5. Compute Similarity



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Given:

- empirical distributions $p_1, p_2, p_3, p_4, \dots$
- sizes of interesting regions $R_1, R_2, R_3, R_4, \dots$

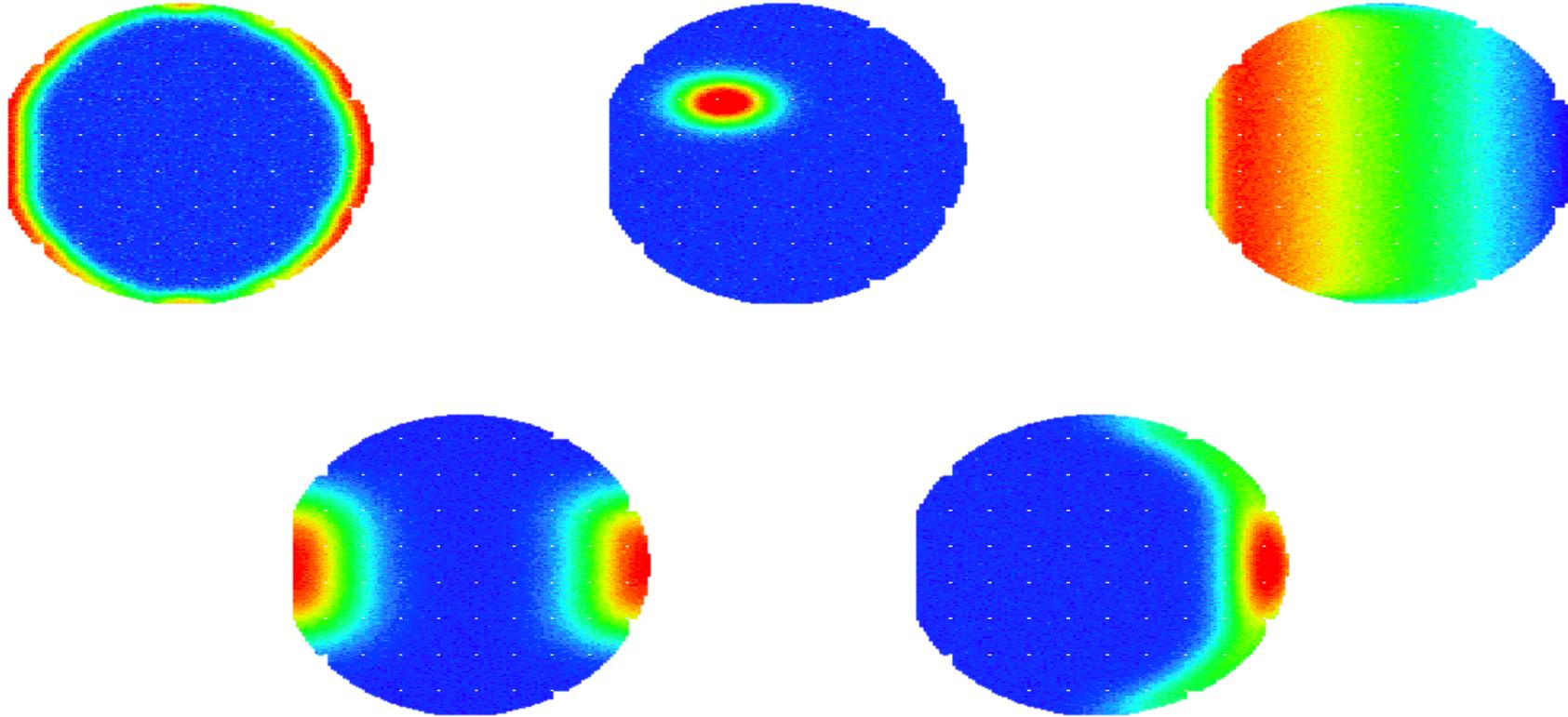
Use Jensen-Shannon Divergence to compute the similarity

- ❖ between wafermaps → **Clustering**
- ❖ to prototype patterns → **Classification**
- ❖ to previously seen wafermaps → **Novelty Detection**
- ❖ etc.

Experiments



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M. Pleschberger et al., "Simulated Analog Wafer Test Data for Pattern Recognition [Data set]", 2019. <https://zenodo.org/record/2542504>

Confusion Matrices



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		Pattern				
		1	2	3	4	5
Cluster	1	200	200		200	200
	2			51		
	3			24		
	4			83		
	5			21		
	6			21		

		Pattern				
		1	2	3	4	5
Cluster	1	200			200	
	2		200			
	3			27		
	4			24		
	5			24		
	6			28		
	7			21		
	8			25		
	9			21		
	10			30		
	11					200

		Pattern				
		1	2	3	4	5
Cluster	1	200				
	2		200			
	3			27		
	4			15		
	5			10		
	6			28		
	7			21		
	8			13		
	9			9		
	10			21		
	11			14		
	12			12		
	13			14		
	14			16		
	15				200	
	16					200

- ❖ **Processing Pipeline**
 - pattern-specific features from analog wafermaps
 - represents wafermap via empirical distribution
- ❖ **Similarity Measure: Jensen-Shannon Divergence**
 - appropriate for histograms/distributions
 - justified via bounds on the Bayes error
- ❖ **Processing Pipeline + Similarity Measure:**
 - separates patterns from each other
 - useful for classification, novelty detection,...

Thank you!